

Elaboration of SnS₂ Thin Films by Ultrasonic Spray for Solar Cell Application

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Abstract

Thin films of tin disulfide (SnS₂) semiconductor have been fabricated using spray pyrolysis method. SnS₂ were deposited from aqueous solution containing SnCl₄, 2H₂O and CS(NH₂)₂ at various molar concentrations. The structural, morphological and optical properties of the obtained films were investigated. XRD and SEM data suggest that good quality of SnS₂ is obtained at 0.08 mol/l. The optical analyses show that the films prepared at 0.08 mol/l present the highest transmittance in the visible region. The obtained results confirm that SnS₂ thin films can be good candidates for solar cells devices. These results are of great importance in the prediction of the good application of SnS₂ thin films in solar cells.

Index terms— sn_s2 thin films; ultrasonic spray; structural properties; optical properties; solar cell.

1 I. INTRODUCTION

considerable attention has been paid for the last few decades to the binary compounds based on the Sn-S system, due to their excellent properties and the high potential use in optoelectronic devices [1][2][3][4]. In particular tin disulfide (SnS₂) was considered as one of very interesting tin sulfides semiconductors. SnS₂ has been known for its potential applications in solar cells as well as electrical switchings [5]. Also SnS₂ belongs to IV-VI group of semiconductor compound with hexagonal crystal structure (a= 0.3648 nm, c= 0.5899 nm) [6]. It has a wide band gap energy (2.88 eV) [7], and n-type electrical conductivity with magnitude depending on the preparation methods.

Thin films of SnS₂ compound has been prepared by different technologies deposition techniques. Such as, chemical bath deposition [8], vacuum thermal evaporation [9], close-spaced sublimation [10], successive ionic layer adsorption and reaction (SILAR) [11], spray pyrolysis [12].

In this paper we report a chemical method called ultrasonic spray, for the deposition of SnS₂ thin films at 330 °C onto ordinary glass substrates. The effect of molar concentration parameter on the films properties and their characterization by X-ray diffraction, chemical analysis, and optical techniques are also reported.

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II. EXPERIMENTAL DETAILS

Tin disulfide thin films were prepared by spraying an alcoholic solution containing tin chloride IV (SnCl₄ (2H₂O)) and thiourea CS(NH₂)₂ on glass substrates using spray pyrolysis process. Substrates were degreased in successive rinses with acetone, ethanol, and distilled water. Then, the total solution was sprayed during 25 min on heated substrates at 330 °C. A set of samples was obtained by changing the precursor molar concentration from 0,05 to 0,08 mol/l in atmospheric pressure.

The films were characterized by means of structural, morphological, and optical methods. The X ray diffraction studies were carried out using a D8 ADVANCED BRUKER diffractometer using a Cu K α radiation ($\lambda=1.5405 \text{ \AA}$) in range of 10-85°, the crystallite size were estimated to study the effect of the molar concentration. The surface morphology of the films was observed using a JEOL, model JSM 6301F Scanning Microscopy by field effect. The surface morphological studies were done with the SEM photographs taken with JEOL model JSM6400 scanning

44 microscope. To have an idea about the surface elemental composition of the film, energy dispersive analysis by
45 X-rays (EDAX) was carried out using EDX spectrometer related to the SEM used before.

46 2 III. RESULTS AND DISCUSSION

47 3 a) Structural characteristics

48 The XRD profile of the ultrasonic sprayed SnS₂ thin films on glass substrates is shown in Fig. 1. The prominent
49 Bragg reflection occurring at about $2\theta = 15.14^\circ$ along with many other weak peaks confirms the polycrystalline
50 nature of the films.

51 In all cases we found that (001) is the preferred orientation, so we can say that all SnS₂ thin films are in
52 hexagonal crystallographic phase (JCPDS 23-0677), with the c-axis perpendicular to the substrate. The average
53 crystallite sizes of the films deposited with different molarities have been calculated using the Scherrer's formula:

54 Where λ , θ and $\Delta 2\theta$ are X-ray wavelength, the Bragg's diffraction angle and the full width at half maxima of
55 the peak corresponding to the θ value, respectively.

56 Crystallite size for samples obtained with different concentrations is shown in fig. 2. It can be observed that
57 the grain size decreased with the molar concentration increasing of sprayed precursor solution from 13.93 nm to
58 9.5 nm.

59 4 b) Morphological characteristics

60 The Fig. 3 shows typical SEM images and EDAX spectra of films deposited with the four studied solution
61 concentrations and at substrate temperature 330 °C taken as example. Microscopic examination reveals that the
62 obtained deposits are uniform and compact with good coverage to the substrate basis. As can be seen, the films
63 morphology depends strongly on the concentration solution of the used precursor. Film deposited at 0.08 mol/l
64 has a continuous and dense structure with a very smooth surface morphology as reveals Fig. 3.d. The EDX
65 spectra of the SnS₂ films recorded in Fig. 3 shows the atomic and weight percentages of the elements present in
66 the films and assure the chemical composition of SnS₂. As can be seen, atomic ratio for the samples increases
67 with concentration solution increasing. Also it can be noted, that the formed film at 0.08 mol/l contain S and Sn
68 with almost 39% and 61% ratio, respectively, which is the most near stoichiometric ratio for SnS₂ composition.
69 In addition the presence of Cl is due to the used precursor, and those of O, N is due to the air.

70 5 c) Optical characteristics

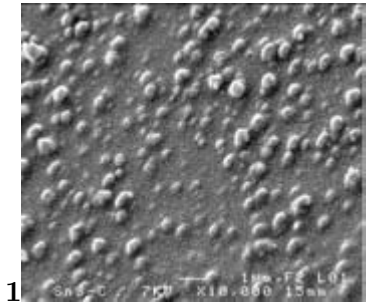
71 Fig. 4 shows the optical transmittance curves as a function of the wavelength for the SnS₂ films deposited at
72 330°C with different molar concentrations. As can be seen the optical transmittance increase with the molarity
73 increasing. The fall of transmittance between 300 nm and 400 nm shows that the films absorb the light ultra
74 violet. Furthermore, film deposited at 0.08 mol/l exhibits interference fringe in the transmittance spectrum and
75 a high transparency than the other films. This is due to the smooth surface of the former. It is well known that
76 rough surface causes the light scattering resulting in transmittance reduction. This explains the low transmittance
77 measured in films deposited with the lowest molar concentration.

78 6 IV. CONCLUSIONS

79 In the present work we have studied the influence of solution properties on SnS₂ thin films deposition by spray
80 pyrolysis. Four molar concentrations were investigated. X-ray diffraction analysis reveals a polycrystalline nature
81 (hexagonal phase) for all the films deposited at $T_s = 330^\circ\text{C}$. It was observed that the grain size is varied between
82 ~ 14 and 9.5 nm. The morphological studies using SEM showed that the films are uniform and compact with
83 good coverage to the substrate basis. EDS results confirm the presence of Sn and S. The optical characterization
84 showed that the films transparent increase with molar concentration increasing. From these values we have
85 suggested that the film deposited at 0.08 mol/l can be a potential candidate as an optical window in solar cells.

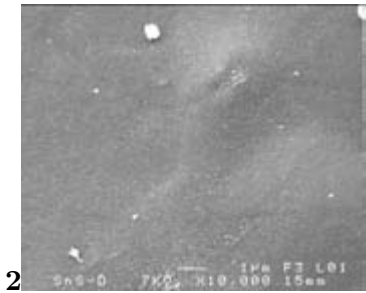
86 7 References Références Referencias

87 Elaboration of SnS₂ Thin Films by Ultrasonic Spray for Solar Cell Application ¹



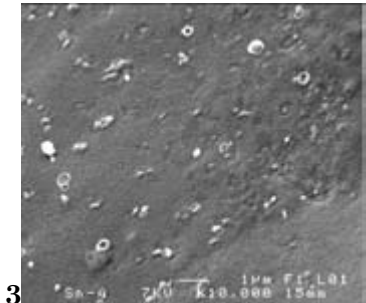
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Figure 1: Fig. 1 :



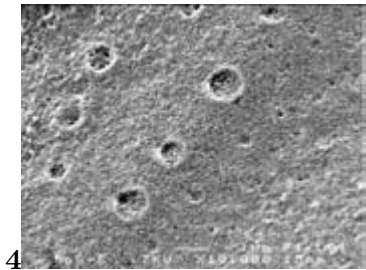
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Figure 2: Fig. 2 :



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Figure 3: Fig. 3 :



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Figure 4: Fig. 4 :

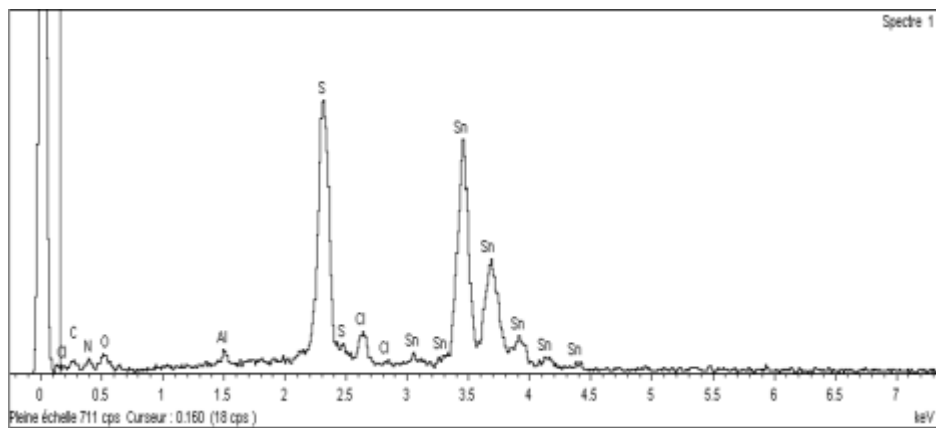


Figure 5:

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